Center Independent Research & Development: GSFC IRAD

Chemical Mechanical Planarization Technology Enabling for Astrophysics Missions



Completed Technology Project (2017 - 2018)

Project Introduction

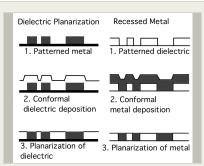
Detector technology for NASA applications is progressing to more complex multilayer circuits to gain advances in array size or detector performance. Chemical Mechanical Planarization (CMP) is a technique that maintains high fabrication yield and increases feature density in multilayer structures. While outside foundries offer CMP for a limited set of materials, we propose to leverage in-house and federal government facilities to develop custom CMP techniques for the specific materials we need, thereby enabling breakthrough enhancements in detectors, multiplexers, and microwave devices for astrophysics missions.

Anticipated Benefits

Chemical Mechanical Planarization technology enabling higher performance detectors, multiplexers, and microwave devices for astrophysics missions.

Primary U.S. Work Locations and Key Partners





CMP planarization processes for dielectrics and metals.

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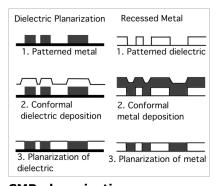
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| Organizations Performing Work | Role | Туре | Location |
|---------------------------------------|----------------------------|------------------|--|
| ☆Goddard Space Flight Center(GSFC) | Lead Organization | NASA Center | Greenbelt, Maryland |
| Department of Commerce(DoC) | Supporting Organization | US Government | Washington, District of Columbia |

Primary U.S. Work Locations

Maryland

Images



CMP planarization processes

CMP planarization processes for dielectrics and metals. (https://techport.nasa.gov/imag e/28230)

Organizational Responsibility

Responsible Mission Directorate:

Mission Support Directorate (MSD)

Lead Center / Facility:

Goddard Space Flight Center (GSFC)

Responsible Program:

Center Independent Research & Development: GSFC IRAD

Project Management

Program Manager:

Peter M Hughes

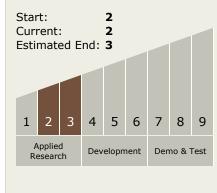
Project Managers:

Megan E Eckart Timothy D Beach

Principal Investigator:

Thomas R Stevenson

Technology Maturity (TRL)





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Technology Areas

Primary:

- TX08 Sensors and Instruments
 - ☐ TX08.1 Remote Sensing Instruments/Sensors
 - ☐ TX08.1.1 Detectors and Focal Planes

Target Destinations

Outside the Solar System, Foundational Knowledge

